

# [PHOTORESIST TRIMMING PROCESS]

## Abstract

A photoresist trimming gas compound is provided which will selectively remove a resist foot or scum from the lower portions of sidewalls of a photoresist. Additionally, the trimmer compound hardens or toughens an upper surface of the photoresist thereby strengthening the photoresist. The trimmer compound includes  $O_2$  and at least one other gaseous oxide and is typically utilized in a dry etching process after a trench has been formed in a photoresist. The other oxide gases, in addition to the  $O_2$ , may include  $CO_2$ ,  $SO_2$  and  $NO_2$ .